

100318690

531 Rec'd PCT 20 DEC 2001

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
CHIBA, Tatsuo, et al.) Atty. Docket No.: TSUK 0005
Serial No. _____ (corresponding to)
PCT/JP00/04028 filed 21 June 2000))
Filed: Herewith)
For: PHOTSENSITIVE ELEMENT,)
PHOTSENSITIVE ELEMENT ROLL,)
PROCESS FOR THE PREPARATION)
OF RESIST PATTERN USING THE)
SAME, RESIST PATTERN, RESIST)
PATTERN LAMINATED)
SUBSTRATE, PROCESS FOR THE)
PREPARATION OF WIRING) Date: 20 December 2001
PATTERN AND WIRING PATTERN)

5/A
D.G.
3-12-02

PRELIMINARY AMENDMENT (A)

BOX: PCT (DO/EO/US)
Assistant Commissioner for Patents
Washington, D. C. 20231

Sir:

Prior to calculating the filing fee, kindly amend the above-captioned application as follows:

IN THE CLAIMS:

Kindly amend claims 20, 22, 29-31 and 40 and replace them with the following:

A1
20. (Amended) A photosensitive element roll according to Claim 1, wherein the above photosensitive element is wound up or rolled around a core.

A2
22. (Amended) A process for preparing a resist pattern which comprises laminating the photosensitive element according to Claim 1 to a substrate for forming a circuit so that the photosensitive resin composition layer is closely contacted to the substrate, irradiating imagewise active light to photocure the exposed portion, and removing an unexposed